Materials Research. 2022; 25:e20210016er
DOI: https://doi.org/10.1590/1980-5373-MR-2021-0016er

Erratum: Characterization of Plasma-deposited a-C:H:Si:F:N Films

In the article "Characterization of Plasma-deposited a-C:H:Si:F:N Films", with DOI: https://doi.org/10.1590/1980-5373-MR-2021-0016, published in Materials Research, 24(suppl. 1):e20210016, on page 6, Figs. 11 and 12, should be as shown below:

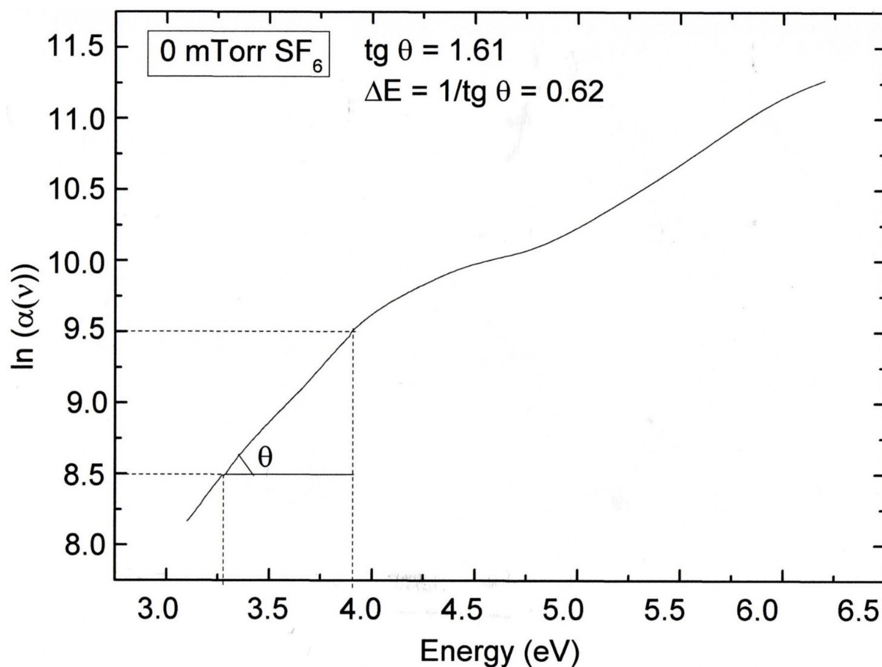

Figure 11. Example (of the unfluorinated film) of the graph allowing the calculation of the Urbach energy.

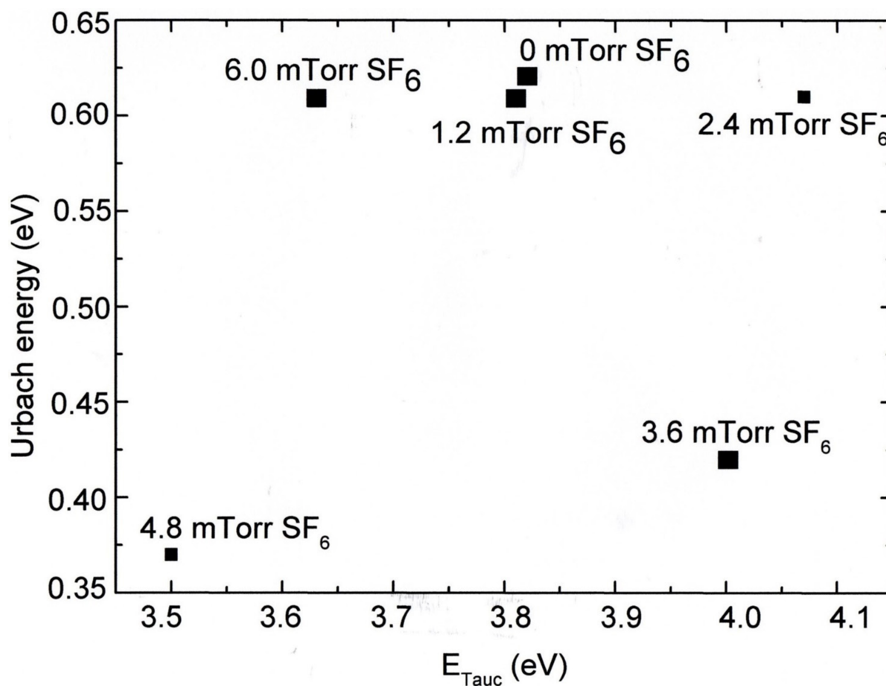

Figure 12. Urbach energy as a function of the Tauc gap. The partial pressure of SF_6 used for each film deposition is given.